


Substitute Form PTO-1449 (Modified) Information Disclosure Statement by Applicant (Use several sheets if necessary) (37 CFR §1.98(b))	U.S. Department of Commerce Patent and Trademark Office	Attorney's Docket No. 10559-863001	Application No. 10/698,782
	Applicant Rex K. Frost et al.		
	Filing Date October 31, 2003	Group Art Unit	

U.S. Patent Documents							
Examiner Initial	Desig. ID	Document Number	Publication Date	Patentee	Class	Subclass	Filing Date If Appropriate
<i>AR</i>	AA	6,492,069	12/2002	Wu, et al.			
<i>AR</i>	AB	6,500,587	12/2002	Ghandehari, et al.			
<i>AR</i>	AC	6,524,752	02/2003	Pierrat			
<i>AR</i>	AD	6,524,755	02/2003	Jin, et al.			
<i>AR</i>	AE	6,569,580	05/2003	Campi, et al.			
	AF						
	AG						

Foreign Patent Documents or Published Foreign Patent Applications								
Examiner Initial	Desig. ID	Document Number	Publication Date	Country or Patent Office	Class	Subclass	Translation	
							Yes	No
	AH							
	AI							

Other Documents (include Author, Title, Date, and Place of Publication)		
Examiner Initial	Desig. ID	Document
<i>AR</i>	AJ	Liebmann, L., "Layout Impact of Resolution Enhancement Techniques: Impediment or Opportunity", <i>International Symposium on Physical Design 2003</i> , Session 7, pp. 110-117, Monterey, CA, April 6-9 (2003).
<i>AR</i>	AK	Liebmann, L., "Resolution Enhancement Techniques in Optical Lithography, It's not just a Mask Problem", <i>Proceedings SPIE, Photomask and Next-Generation Lithography Mask Technology VIII</i> , Vol. 4409, pp. 23-32 (2001).
<i>AR</i>	AL	Nordquist, K., et al., "Critical Dimension and Image Placement Issues for Step and Flash Imprint Lithography Templates", <i>Proceedings of SPIE, 22nd Annual BACUS Symposium on Photomask Technology</i> , Vol. 4889, No. 129, pp. 1143-1150 (2002).
<i>AR</i>	AM	Petersen, J., et al., "Development of a Sub-100nm Integrated Imaging System Using Chromeless Phase-Shifting Imaging with Very High NA KrF Exposure and Off-axis Illumination", <i>Proceedings SPIE, Design, Process Integration, and Characterization for Microelectronics</i> , Vol. 4692, pp. 298-311 (2002).
<i>AR</i>	AN	Scheid, G., et al., "Contact Holes: Optical Area Measurement Predicts Printability and is Highly Repeatable", presented at Photomask Japan 2001, Paper 4409-11, pp. 1-6 (2001).
<i>AR</i>	AO	Zhang, H., et al., "Compact Formulation of Mask Error Factor for Critical Dimension Control in Optical Lithography", <i>Proceedings SPIE, Metrology, Inspection, and Process Control for Microlithography XVI</i> , Vol. 4689, pp. 462-465 (2002).
	AP	

Examiner Signature 	Date Considered 10/06
EXAMINER: Initials citation considered. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.	